## Maglen Ebeam Wafer Imaging System

**Tony Luo** 





### **Agenda**

- Introduction
- Review of Previous Works
- Progress
- Miniaturization
- Advantages
- Summary

## Copyright © 2016 All rights reserved

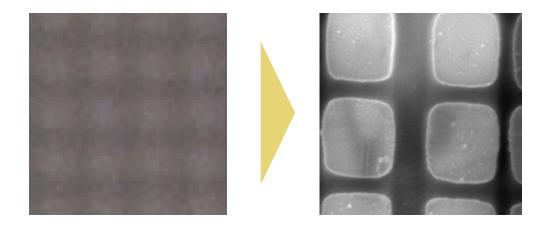
### Introduction

• Optical Microscope VS Scanning Electron Microscope

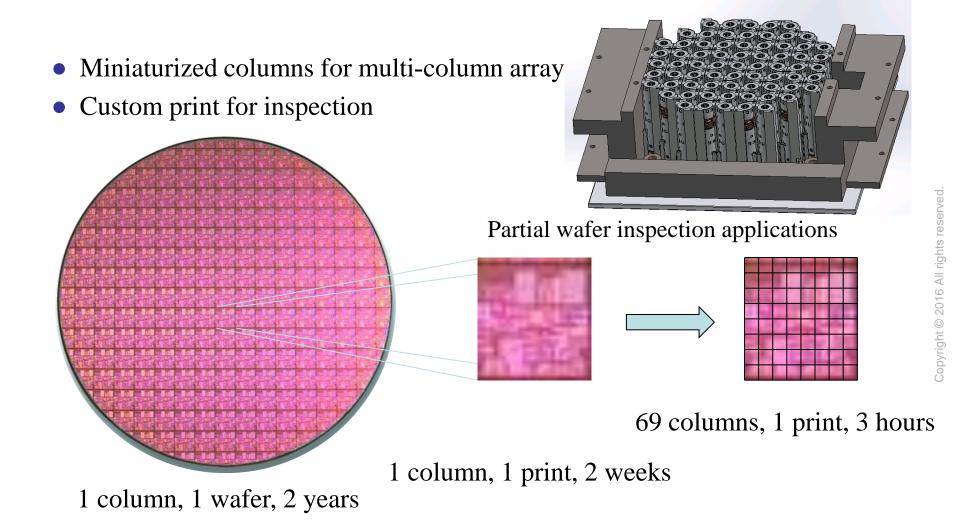
Fast Slow

Blur Clear

193nm 0.04nm

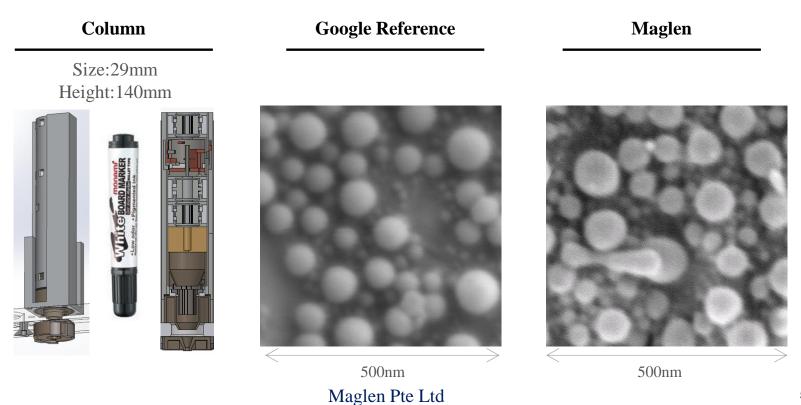


### **Review of Previous Works**



### **Progress**

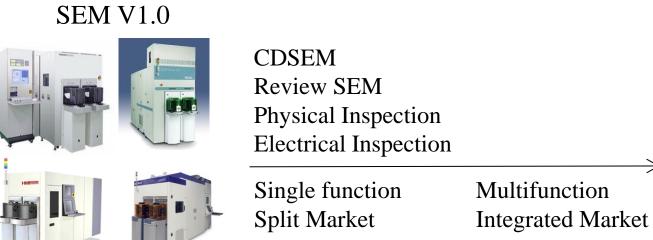
- Diameter: 29mm -> 20mm future
- 2 High resolution of 2nm with high beam current of 1nA



### **Small array of columns**

• A Multi-Column not for parallel imaging purposes...

...but for multi-functional common platform



Maglen Ebeam Wafer Imaging System

**SEM V2.0** 

### Why so many SEMs

• High resolution is too hard, and SEM is just too slow. Therefore, column hardware designs must focus on some applications, while compromise on others.



### Miniaturization allows common platform

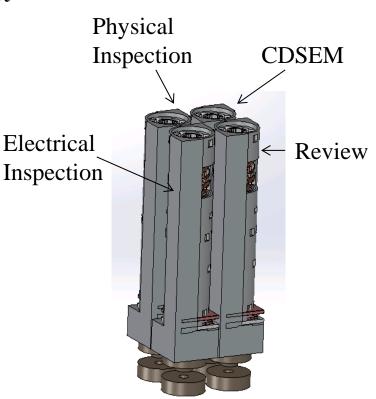
2X2 small array to consolidate the market

4 Markets in 1

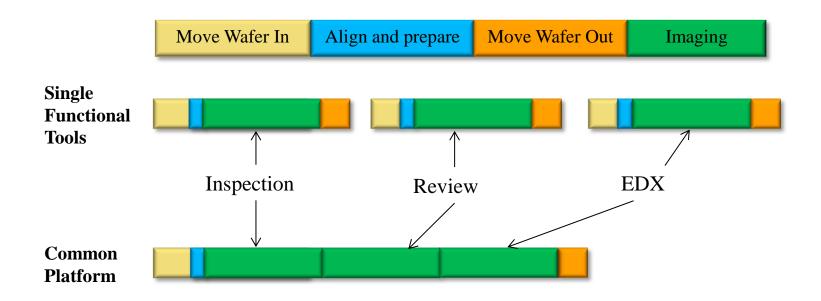
Change of process, higher efficiency

Reduce the redundancy

Dynamic throughput control



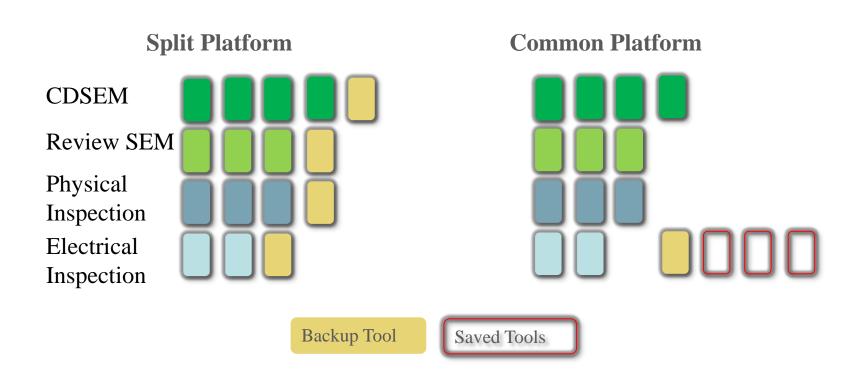
### Change of process, higher efficiency



Common platform can quickly switch the column for the job, reduce non-productive efforts, enhance the efficiency

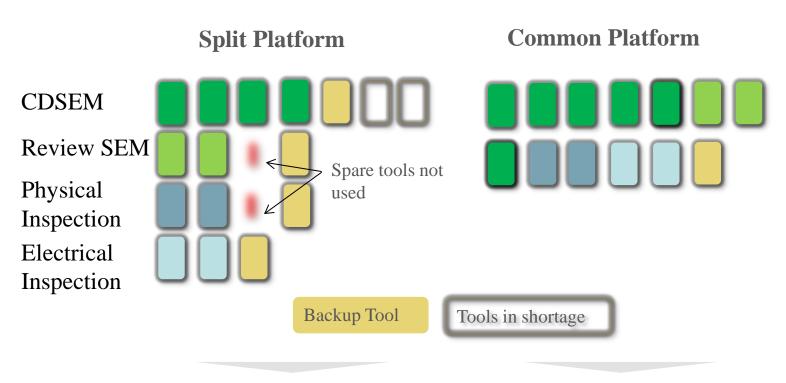
# Copyright © 2016 All rights reserved.

### **Reduce the Redundancy**



When a SEM tool of any kind failed, it can be replaced by a common platform tool, and less redundancy is needed.

### **Dynamic throughput control**



- Limited by individual tool throughput
- Spare tools can not be switched for other modes

 Adjustable throughputs according to demands

Throughput distribution can be adjusted without purchasing new hardware.

### **Summary**

Miniaturization allows common platform ebeam imaging system

Consolidating the market allows economy of scale

Performance and efficiency both improves with independent optimization

